

Notice of References Cited	Application/Control No. 10/711,897	Applicant(s)/Patent Under Reexamination YANG ET AL.	
	Examiner Toniae M. Thomas	Art Unit 2822	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2002/0197890 A1	12-2002	Mizuno et al.	438/794
*	B	US-5,811,329	09-1998	Ahmad et al.	438/233
*	C	US-6,372,569 B1	04-2002	Lee et al.	438/229
*	D	US-6,455,405 B1	09-2002	Ku, Shao-Yen	438/585
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	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf et al., "Chemical Vapor Deposition of Amorphous and Polycrystalline Films," Silicon Processing for the VLSI Era - Vol 1: Process Technology, Lattice Press, 1986, pp. 182-185.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.